

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of Invention

TWO-SIDED CHEMICAL MECHANICAL POLISHING PAD FOR
SEMICONDUCTOR PROCESSING

Application Number :

Confirmation Number:

First Named Applicant: Raymond Khoury

Attorney Docket Number: FIS920030277

Art Unit:

Examiner:

Search string: (5212910 or 5533923 or 5882251 or 6120366 or 6458023 or 6572446 or 6623337
or 20030034131).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

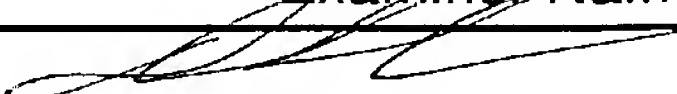
init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
D37	1	5212910	1993-05-25	Breivogel et al.			
	2	5533923	1996-07-09	Shamouilian et al.			
	3	5882251	1999-03-16	Berman et al.			
	4	6120366	2000-09-19	Lin et al.			
	5	6458023	2002-10-01	Moon			
	6	6572446	2003-06-03	Osterheld et al.			
D37	7	6623337	2003-09-23	Scott et al.			

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
D37	1	20030034131	2003-02-20	Park et al.			

Signature

Examiner Name	Date
	9/6/04